

Ifw

Docket Number: 081468-0307331
Client Reference: P-1774.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of

VAN SANTEN et al.

Group Art Unit: 2851

Application No.: 10/743,271

Examiner: Unassigned

Filed: December 23, 2003

Confirmation No.: 4441

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

January 7, 2005

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

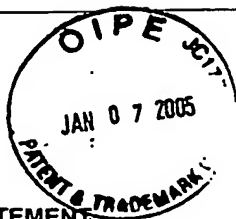
Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DIERICHS (081468-0308270)	10/775,826	02/11/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.



Atty. Dkt. No.	M#	Client Ref.
	307331	P-1774.000-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	VAN SANTEN et al.
Appln. No.	10/743,271
Filing Date:	December 23, 2003
Examiner:	Unknown
Group Art Unit:	2851

Date: January 7, 2005

Page 1 of 4

U.S. PATENT DOCUMENTS

Examiner's Initials	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
HN	AR 3,573,975	04/1971	DHAKA et al.	117	212	
	BR 3,648,587	03/1972	STEVENS	95	44	
	CR 4,346,164	08/1982	TABARELLI et al.	430	311	
	DR 4,390,273	06/1983	LOEBACH et al.	355	125	
	ER 4,396,705	08/1983	AKEYAMA et al.	430	326	
	FR 4,480,910	11/1984	TAKANASHI et al.	355	30	
	GR 4,509,852	04/1985	TABARELLI et al.	355	30	
	HR 5,040,020	08/1991	RAUSCHENBACH et al.	355	53	
	IR 5,121,256	06/1992	CORLE et al.	359	664	
	JR 5,610,683	03/1997	TAKAHASHI	355	53	
	KR 5,715,039	02/1998	FUKUDA et al.	355	53	
	LR 5,825,043	10/1998	SUWA	250	548	
	MR 5,900,354	05/1999	BATCHELDER	430	395	
HN	NR 6,191,429	02/2001	SUWA	250	548	

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
HN	OR WO 99/49504	09/1999	PCT	FUKAMI et al.	X		X	
	PR EP 0023231	02/1981	EUROPE	TABARELLI et al.	X			
	QR EP 0418427	03/1991	EUROPE	MIYAKE	X		X	
	RR EP 1039511	09/2000	EUROPE	MURAKAMI et al.	X		X	
	SR DD 224448	07/1985	GERMANY	HESSE et al.		X		
	TR DD 242880	02/1987	GERMANY	KUCH		X		
	UR FR 2474708	07/1981	FRANCE	LETELLIER		X		
	VR JP 62-065326	03/1987	JAPAN	MORIUCHI	X			
	WR JP 62-121417	06/1987	JAPAN	NAKAZAWA	X			
	XR JP 63-157419	06/1988	JAPAN	NAKASUJI	X			
	YR JP 04-305915	10/1992	JAPAN	OZEKI et al.	X			
	ZR JP 04-305917	10/1992	JAPAN	OZEKI et al.	X			
HN	AAR JP 06-124873	05/1994	JAPAN	TAKAHASHI	X		X	

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

HN	BBR	M. SWITKES et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001			
	CCR	M. SWITKES et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356			
HN	DDR	M. SWITKES et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002			

Examiner: H. Nguyen Date Considered: 6/13/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office				Atty. Dkt. No.	M#	Client Ref.			
				307331		P-1774.000-US			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant: VAN SANTEN et al.					
				Appln. No. 10/743,271					
				Filing Date: December 23, 2003					
				Examiner: Unknown		Group Art Unit: 2851			
Date: January 7, 2005 Page <u>2</u> of <u>4</u>									
U.S. PATENT DOCUMENTS									
Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)		
HN	AR	6,560,032	05/2003	HATANO	359	656			
	BR	6,603,130	08/2003	BISSCHOPS et al.	250	492.1			
	CR	6,633,365	10/2003	SUENAGA	355	53			
	DR	2002/0163629	11/2002	SWITKES et al.	355	53			
	ER	2003/0123040	07/2003	ALMOGY	355	69			
	FR	2003/0174408	09/2003	ROSTALSKI et al.	359	642			
	GR	2004/0075895 A1	04/2004	LIN	359	380			
HN	HR	2004/0109237 A1	06/2004	EPPLÉ et al.					
	IR								
FOREIGN PATENT DOCUMENTS									
		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
HN	JR	JP 07-220990	08/1995	JAPAN	FUKUDA et al.	X			
	KR	JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
	LR	JP 10-255319	09/1998	JAPAN	SUENAGA et al.	X			
	MR	JP 10-303114	11/1998	JAPAN	SUWA	X		X	
	NR	JP 10-340846	12/1998	JAPAN	KUDO	X		X	
	OR	JP 2001-091849	04/2001	JAPAN	AIZAKI et al.	X			
	PR	JP 07-132262	05/1995	JAPAN	HIRAKAWA et al.	X			
	QR	JP 58-202448	11/1983	JAPAN	KAWAMURA et al.	X			
	RR	WO 2004/019128	03/2004	PCT	OMURA et al.	X		X	
	SR	WO 03/077037	09/2003	PCT	ROSTALSKI et al.	X		X	
HN	TR	WO 03/077036	09/2003	PCT	SCHUSTER	X			
	UR								
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)									
HN	VR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002							
	WR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997							
	XR	B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269							
	YR	G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72							
	ZR	S. OWA et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003							
HN	AAR	S. OWA et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)							
Examiner <u>H. Nguyen</u>					Date Considered: <u>6/13/05</u>				
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.									

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office				Atty. Dkt. No.	M#	Client Ref.		
				307331		P-1774.000-US		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant: VAN SANTEN et al.				
				Appln. No. 10/743,271				
				Filing Date: December 23, 2003				
				Examiner: Unknown		Group Art Unit: 2851		
Date: January 7, 2005 Page <u>3</u> of <u>4</u>								
U.S. PATENT DOCUMENTS								
Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)	
HW	AR	6,236,634 B1	05/2001	LEE et al.	369	112		
HW	BR	2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492		
FOREIGN PATENT DOCUMENTS							English Abstract	Translation Readily Available
		Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No
HW	CR	DD 206 607	02/1984	GERMANY	WESTPHAL et al.			X
	DR	DD 221 563	04/1985	GERMANY	PFORR et al.			X
	ER	JP 11-176727	07/1999	JAPAN	SHIRAISHI		X	
	FR	JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.		X	
	GR	WO 2004/053950 A1	06/2004	PCT	OWA		X	
	HR	WO 2004/053951 A1	06/2004	PCT	MAGOME et al.		X	
	IR	WO 2004/053952 A1	06/2004	PCT	MAGOME et al.		X	
	JR	WO 2004/053953 A1	06/2004	PCT	NEI et al.		X	
	KR	WO 2004/053954 A1	06/2004	PCT	NEI et al.		X	
	LR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.		X	
	MR	WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.		X	
	NR	WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.		X	
	OR	WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.		X	
	PR	WO 2004/053959 A1	06/2004	PCT	SHIRAI		X	
HW	QR	WO 2004/053596 A2	06/2004	PCT	GRAUPNER		X	
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)								
HW	RR	Nikon Precision Europe GmbH, "Investor Relations – Nikon's Real Solutions", May 15, 2003						
	SR	H. KAWATA et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36						
	TR	J.A. HOFFNAGLE et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309						
	UR	B.W. SMITH et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003						
	VR	H. KAWATA et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177						
HW	WR	G. OWEN et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036						
	XR							
	YR							
Examiner <u>H. Nguyen</u>						Date Considered: <u>6/13/05</u>		
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.								

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty.
Dkt. No.

M#

Client Ref.

307331

P-1774.000-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: VAN SANTEN et al.

Appln. No. 10/743,271

Filing Date: December 23, 2003

Date: January 7, 2005

Page 4 of 4

Examiner: Unknown

Group Art Unit: 2851

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
HW	ZR 2004/0119954	06/2004	KAWASHIMA et al.	355	30	
HW	AAR 2004/0125351	07/2004	KRAUTSCHIK et al.	355	53	
	BBR					
	CCR					
	DDR					
	EER					
	FFR					
	GGR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
HW	HHR WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X		X	
I	IIR WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X		X	
J	JJR WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X		X	
HW	KKR JP 2004-193252	07/2004	JAPAN	Not Available	X			
	LLR							
	MMR							
	NNR							
	OOR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

HW	PPR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
	QQR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
	RRR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
	SSR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	TTR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
HW	UUR	B. LIN, "The k_3 coefficient in nonparaxial MNA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)			
	VVR				
	WWR				
	XXR				
	YYR				
	ZZR				

Examiner

H. Nguyen

Date Considered:

6/13/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

Docket Number: 081468-0307331
Client Reference: P-1774.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE.

In Re the Application of
ELMAR VAN SANTEN et al.
Application No.: 10/743,271

Group Art Unit:

Examiner: Unassigned

Filed: December 23, 2003

Confirmation No.: Unassigned

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	Joeri LOF et al.	10/705,805	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Joeri LOF et al.	10/705,783	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Klaus SIMON et al.	10/724,402	12/01/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Joannes T. DESMIT et al.	10/705,804	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Arno J. BLEEKER	10/715,116	11/18/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Bob STREEFKERK et al.	10/719,683	11/24/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Joeri LOF et al.	10/705,816	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.



Atty. Dkt. No.	M#	Client Ref.
081468	0307331	P-1774.000-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: February 20, 2004

Page

1

of

1

Applicant: Helmar VAN SANTEN et al.

Appln. No.: 10/743,271

Filing Date: December 23, 2003

Examiner: Unassigned

Group Art Unit: Unassigned

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
HW	AR 2004/0000627A1	01/01/2004	Karl-Heinz SCHUSTER			
	BR 6,600,547	07/29/2003	WATSON et al.			
HW	CR 2004/0021844 A1	02/05/2004	Yutaka SUENAGA			
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
	OR							
	PR							
	QR							
	RR							
	SR							
	TR							
	UR							
	VR							
	WR							
	XR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

HW	YR	H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3			
HW	ZR	S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.			
	AAR				
	BBR				
	CCR				
	DDR				

Examiner

H. Nguyen

Date Considered:

6/13/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.